

# A comprehensive review: SnO<sub>2</sub> for photovoltaic and gas sensor applications

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Tin oxide is remarkable material in today's research era due to its unique properties in electrical and optical fields. Due to its wide band gap (3.6 eV), it has been used as a core material in many important applications in the field of optoelectronics, spintronics, photovoltaic, thin-film transistors, photocatalysis, dielectrics, sensors and transparent electronic devices. Thin film technology provides many advantages towards photovoltaic area which includes low cost, less material and energy consumption and easy to access. Fabrication of photovoltaic cells by SnO<sub>2</sub> thin films can open the different technological routes for future generation with excellent conversion efficiencies which may range 15% to 20%. It is one of the best candidates for gas sensor applications too with highest sensitivity and selectivity behavior, good oxidizing power, strong chemical bonding, non toxicity and unique transport properties. Tin oxide thin films with various combinations of materials can be synthesized by chemical and physical routes. The detailed advancement in various preparation methods and characterization techniques including X-ray diffraction, atomic force microscopy and X-ray photoelectron spectroscopy have been presented and discussed by authors. Characteristics measurement by Valence Band Structure, Photoluminescence Intensity and Scanning Electron Microscope has been also reported with their performance, effect of solar energy conversion efficiency and quick response time in case of gas sensors. Prospective areas of SnO<sub>2</sub> research for photovoltaic and gas sensor applications has been discussed and summarized by the authors. The obtained results will illustrate the possibilities of scheming Physical, chemical, magnetic and optical properties of SnO<sub>2</sub> for sensing devices and photovoltaic applications.

**Keywords:** Tin oxide, Photovoltaic, Thin film, Gas sensors

## 1 Introduction

Material science is the systematic study of any material to find out its various characteristic and properties. It includes range of applications from manufacturing nanotechnology devices to constructing new materials at atomic level. In recent scenario we are facing many issues related to conventional sources of energy, global warming, contamination of soil and water, climate change, sanitations etc. Our centre of concern is to reduce these problems by introducing new technologies using advance materials. Nanotechnology and thin films are playing an important role to deal with such type of problems. With the help of this, performance of existing materials can be improved and new functional materials can be developed as discussed by<sup>1</sup>, different types of materials are being used these days which have the potential to prevent and remove pollutants from environment, act as cleaner for industrial waste, advance sensing, photo-catalytic and photovoltaic properties. They can be also use as good chemical reactors in water splitting, organic material

in pigments, to improve antimicrobial effect<sup>2</sup> and photocatalytic degradation. Metallic nanomaterials have fascinated researchers due to its potential applications in the field of biomedical sciences and engineering. Metal cation and oxide anion forms metal oxide. A strong covalent bond is visible in those metals which have high oxidation states. Transition metal (TM) oxides play an important role in catalytic activity and semiconductor properties. It has an extra ordinary potential as base materials in rising new technologies like optoelectronics, spintronics, photovoltaics, thin-film transistors, Photocatalysis, dielectrics, sensors and other transparent electronic devices<sup>3-7</sup>. TM oxides are the most useful multifunctional materials which have unique surface properties, high transmittance in the ultraviolet-visible region and semi-conductivity<sup>8</sup>. Presently most of research work is based on these metals to enhance their applications in different field because it not only provides good scopes to study the optical, electrical and thermal properties in quantum-confinement, but also offers important insights for understanding the functional units in fabricating electronic, optoelectronic, and magnetic devices of nano scale

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dimensions<sup>9</sup>. Wide band gap and remarkable transport properties makes metal oxides as an emerging material nowadays. The most investigated metal oxides are ZnO, TiO<sub>2</sub> and SnO<sub>2</sub> due to its exclusive worldwide useful applications. Tin oxide is the most usable candidate for photovoltaic studies due to earth-abundant, inexpensive and non-toxicity. Centre of investigation of this research work is to explore more about functionality of SnO<sub>2</sub> and to find out possible areas of research work for future applications in photovoltaics and gas sensors.

## 2 Overview of Tin Oxide and its Properties

From the past few decades Semiconducting (Metal) oxides such as ZnO, TiO<sub>2</sub> and SnO<sub>2</sub><sup>10</sup> have been proved to be an important class of transparent conducting oxides (TCO) for applications in solar cells and gas sensors. Due to their low electrical resistivity and high transmittance in the visible range, Tin Oxide is the most familiar material for optoelectronic applications<sup>11</sup>. The wide band gap (3.6 eV) and high excitation binding energy (130 MeV) makes Tin Oxide a suitable candidates for these applications. It is the only oxide of group IV which displays good conductivity and transparent in visible range<sup>12-14</sup> (300 nm- 800 nm). Bulk SnO<sub>2</sub> cannot attain efficient ultraviolet (UV) emission due to the dipole-forbidden rule. Where as pure SnO<sub>2</sub> generally exhibit strong n-type conduction and the lack of p-type conduction. To understand the optical activity and UV emission of this material, some researchers preferred to use doping methods to modify its rutile tetragonal type structure and electronic structure. Figure 1 shows the tetragonal structure of pure and TM doped SnO<sub>2</sub> thin films<sup>15</sup>. The authors have prepared pure SnO<sub>2</sub> and Mn (5%) doped SnO<sub>2</sub> thin films by Pulsed Laser Deposition (KrF excimer) Si substrate (001). Pellets have been prepared under 160 KN pressure with the help of solid state reaction technique. Laser energy density was kept at 2 J/cm<sup>2</sup> and the pulse repetition rate was kept 10 Hz for both the samples. Structural morphology of material is clearly visible by AFM measurements as shown in Fig.1.

## 3 Methodology

There are numerous deposition techniques used to grow SnO<sub>2</sub> films either doped or undoped including chemical vapor deposition, spray pyrolysis, thermal evaporation, sol-gel, and sputtering. Recently, pulsed-laser deposition (PLD) has been used to grow various high-quality thin films for photovoltaic and gas sensor applications<sup>16-17</sup>.

## 3.1 Chemical deposition technique

### 3.1.1 Chemical vapor deposition (CVD)

CVD is a chemical procedure of Vacuum deposition method in which the gaseous precursors is moved into a chamber with the substrate. Through the chemical reaction between the precursor and the substrate, the thin film of required thickness can be obtained at high temperature. This is a popular process in semiconductor industry to fabricate high quality and high performance semiconductors<sup>18</sup>. There are many CVD methods to fabricate thin films including thermal chemical vapor deposition, APCVD (Atmospheric-pressure CVD), MOCVD (Metalorganic chemical vapor deposition), PECVD (Plasma-enhanced chemical deposition), LCVD (Laser Assisted Vapor Deposition), and PACVD (Photo-assisted chemical vapor deposition).

### 3.1.2 Atomic layer deposition (ALD)

Atomic layer deposition method it is also a vapor phase deposition method. In this method the reaction between gaseous precursors and substrate happens consecutively one at a time. For this reaction two or more gaseous precursors are used to obtained thin film of desired thickness. ALD is a stepwise procedure, precursors react only with the available substrate and no more reaction occurs after the surface is saturated .Therefore it is slower process but has the advantage of precise thickness control of film even on lower temperature<sup>19-20</sup>.

### 3.1.3 Sol-gel method

Sol-Gel is a chemical solution deposition method in which precursor material form a solution called 'sol'. This 'sol' has been deposited on the substrate

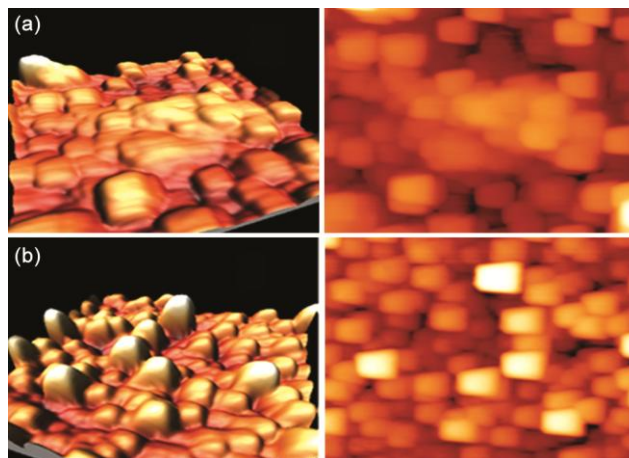


Fig. 1 – 3D AFM images of (a) pure SnO<sub>2</sub> and (b) doped Sn<sub>0.995</sub>Mn<sub>0.005</sub>O<sub>2</sub> thin films.

through highly controlled process. Sol-Gel method involves gelation process, where the precursor material transfers from a liquid ‘sol’ to solid ‘gel’ form<sup>20</sup>. This solution is known as a sol-gel which is a constant combination of suspended precursor particles and substrate. Spin coating, dipping and spraying these methods comes under the Sol-gel method. A brief description of different methods to synthesis a thin film for its useful applications is shown in tabular form in Table 1.

### 3.2 Physical deposition technique

#### 3.2.1 Molecular beam epitaxy (MBE)

MBE has the advantages of both chemical and physical methods for thin film fabrication. In MBE the films are deposited on single-crystal substrates by slowly evaporating the material onto substrates held at a temperature appropriate for epitaxy, chemical reaction, and re-evaporation of excess reactants. In this method, the deposition of target material is completed in the form of layers but one layer at a single time. Layer by layer growth finely controlled by high speed shutters and can be monitor desired thickness of thin film<sup>21-22</sup>.

#### 3.2.2 Sputtering

Sputtering is a physical thin film deposition method in which surface atoms are released by bombarding of ions on surface of a target material and then it come to rest on the substrate. In this deposition method Nobel gas Argon is taken as a target material at low temperature. Normally Nobel gas is less reactive so it behaves neutral for any chemical reaction in the chamber, because of this it is a fast and an authentic method. Sputtering is clearly an etching procedure, so it is useful for surface cleaning application<sup>22</sup>. We classified process of sputtering in the following terms: Diode Sputtering, Reactive Sputtering, Bias Sputtering and Ion-Beam Sputtering. Diode Sputtering: In Diode sputtering material is to be deposited (cathode) on the target substrate (electrode) in a glow discharge vacuum chamber. Usually thin films pure metals can be deposited in the

presence of noble gas (Ar) with metal targets. Radio Frequency (RF) Sputtering: This is suitable for the dielectric (electrically non-conducting) material and insulating targets. If the frequencies are less than about 50 kHz then electron (cathode) and ions (anode) can be move easily in plasma. In the case of frequencies above about 50 kHz then ions can be unable to move in plasma. Generally a frequency of 13.56 MHz is used which is radiate a certain amount of energy without interfering with communications<sup>23</sup>. Magnetron Sputtering: In the magnetron sputtering process the magnetic fields converts into the electric fields. Strong magnets are use to confine the glow discharge. Sputtering with a transverse magnetic field generates several important alterations of the basic processes. Ion-Beam Sputtering: Sputtering of Ion beams generates in and extracted from glow discharges from the surface. This is very useful method for deposition of special materials on desired small substrate area.

#### 3.2.3 Thermal evaporation

In thermal evaporation, the material is heated in a vacuum chamber until its surface atoms have sufficient energy to leave the surface. The evaporated material then condensed on the substrate for synthesis of thin film of desired thickness.

#### 3.2.4 Spray pyrolysis deposition

In Spray pyrolysis the deposition of thin film can be occurred by spraying a solution onto a heated surface. Spray pyrolysis consists of the chemical dissociation or evaporation of droplets containing a solute of the desired nanomaterials<sup>24</sup>. Hence it has been follow by both gas-phase and liquid-phase methods. Spray pyrolysis method is based on forming an aerosol from various precursor solutions, which could be a solution of metallic salts or a colloidal solution<sup>25</sup>. It is a Non-reversible process which provides high efficiency.

#### 3.2.5 Laser evaporation

The laser evaporation technique is used as the thermal source to vaporize or removing materials

Table 1 – A glance of various preparation methods of thin film deposition of SnO<sub>2</sub> material.

Thin Films Deposition Techniques				
Chemical Process (Nonequilibrium reaction)				Physical Process (Equilibrium reaction)
Plating	Sol Gel	CVD	Evaporation	Sputtering
Electroplating	Dipping	MOCVD	Ion Plating	RF
Electrolysis	Spraying	PECVD	MBE	DC
Flame Hydrolysis deposition (FHD)	Spin Coating	ALD	Laser ablation & Electron Beam	Magnetron

from a solid surface, and preparation of thin film. The laser evaporation is high vacuum technique, where the source of powder is kept outside the vacuum system. Usually, laser ablation refers to removing material with a pulsed laser, but it is possible to ablate material with a continuous wave laser beam if the laser intensity is high enough<sup>26</sup>.

### 3.2.6 Pulsed laser deposition (PLD)

Pulsed laser deposition uses energy from a laser source to excite the target surface. The electronic excitation, heating and physical ablation of the surface atoms and molecules occurs due to high energy. The molecules which are ablated from the surface form a plasma plume which is directed to the substrate where deposition process takes place. The change in chemical and physical parameters which take place at target and substrate depends on the type of target material, energy of laser light, intensity, and distance between the target substrate<sup>21</sup>.

## 4 Tin Oxide as Photovoltaic Cell

The working of PV materials for photovoltaic application is based on the photo-electric effect. In this effect the exposed PV material converts electromagnetic energy (Sunlight) to Electric energy. Photovoltaic cell is the most demanding renewable sources of energy<sup>27</sup>. It has lots of advantages compared to other forms of energy like fossils fuels and petroleum. It is a promising and sustainable energy source for the high energy demand without any harm in our atmosphere. Ke *et al.*<sup>28</sup> have discussed about SnO<sub>2</sub> ETLs in perovskite solar cell. They used the unique properties of SnO<sub>2</sub> like wide band gap, high electron mobility and good antireflection to get excellent PCE of 16.02%. SnO<sub>2</sub> ETLs Synthesized by spin coating of SnCl<sub>2</sub>.2H<sub>2</sub>O precursor prepared at a room temperature and followed by thermal annealing in air at 180 °C for 1 h. They summarized in their study that low-temperature solution-processed SnO<sub>2</sub> is an excellent ETL material for high performance perovskite solar cells. Bouras *et al.*<sup>29</sup> reported on the structural, optical and electrical properties of Nd-doped SnO<sub>2</sub> thin films deposited by the RF magnetron sputtering at different temperatures. Through XRD and XPS analysis they showed the crystallinity and phase composition of the films. The polycrystalline rutile structure of the films is improving with increasing the growth temperature and the layers exhibit a SnO<sub>2</sub> structure. PL measurements showed that the films exhibit very strong and well defined emission peaks characteristics

of Nd atoms whose the XPS 3d core level revealed the 3p ionic state. PLE spectroscopy revealed an efficient resonant energy transfer from the SnO<sub>2</sub> host matrix to the Nd<sub>3p</sub> ions as well as direct excitation lines allowing us identification of some energy levels of Nd<sub>3p</sub> ions. The down-shifting functionality was concluded. The electrical properties of the films performed by the Hall Effect measurement showed the n-type character of the films and improvement of the carrier concentration, resistivity and mobility with deposition temperatures upto 300°C. The optimum condition enabling the best electrical conductivity and the highest PL intensity was found for deposition at 300 °C. The application of this Nd–SnO<sub>2</sub> optimized layer to CIGS solar cells showed the highest short circuit current density, and overall the best cell efficiency, which can be attributed to good TCO properties and photon conversion process provided by the Nd-doped tin oxide films. Zhu *et al.*<sup>30</sup> successfully exploited the solution processed SnO<sub>2</sub> nanocrystals to develop as an efficient ETL in the inverted thin film Photovoltaic solar cell. They suggested that due to some novel properties SnO<sub>2</sub> is more compatible than ZnO and TiO<sub>2</sub>. In this paper they first prepared highly crystalline SnO<sub>2</sub> NCs with hydrothermal method and then applied it as an ETL in PVSCs. Due to their high crystallinity it forms a thick layer and preserve the device from O<sub>2</sub> and Water. So it improves the stability of device with the high PCE 18.8%. Ikhmayies<sup>31</sup> presented a review of TCOs prepared for use in solar cells. Thin films of SnO<sub>2</sub>, SnO<sub>2</sub>:F, ZnO and ZnO:Al were prepared and characterized by X-ray diffraction (XRD), scanning electron microscopy (SEM), current–voltage (I–V) characteristics and transmittance spectroscopy. Huang *et al.*<sup>32</sup> have compared the performance of individual SnO<sub>2</sub> Thin film and TiO<sub>2</sub> Thin film with the composite SnO<sub>2</sub>-TiO<sub>2</sub> thin film. They resulted that composite layer of thin film is giving best Power Conversion Efficiency 14.80%, which is higher than PCEs of devices based on individual SnO<sub>2</sub> layer and sintered TiO<sub>2</sub> layer.

Dong *et al.*<sup>33</sup> reported in their paper study of compact SnO<sub>2</sub> ESL and compact TiO<sub>2</sub> ESL and their PCEs. Fabrication of thin films based on sol-gel method. They applied various characterizations on films like SEM, J-V Curves, PL, XRD, IPCE. Wang *et al.*<sup>34</sup> discussed that low temperature processed tin oxide (SnO<sub>2</sub>) is an outstanding material for fabricating Perovskite solar cell. They performed experiment on SnO<sub>2</sub> ESLs to receive high device efficiency by PEALD process at below 100C temperature and get

100°C PCEs approximate 18%. They applied Spin coating and ALD method to prepare SnO<sub>2</sub> ESL thin film. Xiong *et al.*<sup>35</sup> investigated in this paper that the HTP SnO<sub>2</sub> with suitable Mg doping is the very good alternative ESL for Photovoltaic application. This process enhances the power conversion efficiency of solar cell approximately 14.60% and nearly 92.8% enhancement compared to that with undoped SnO<sub>2</sub>. Roose *et al.*<sup>36</sup> have summarized in their paper about the UV instability of Perovskite solar cell using my TiO<sub>2</sub>. They adopted the conclusion that this instability can be replaced by using m-SnO<sub>2</sub> thin film. In their experiments they achieved the high efficiency approximately 16.4%. Solar cell is fabricated by Ga doped SnO<sub>2</sub> film. Ren X *et al.*<sup>37</sup> concluded that Nb doped SnO<sub>2</sub> ETL enhance electron mobility, surface morphology, conductivity, electron extraction and also achieved a higher PCE of 17.57%. Sinha<sup>38</sup> has successfully fabricated ZnO-SnO<sub>2</sub> composite thin film by pulsed laser deposition (PLD) technique and find this technique very suitable for fabrication due to uniformity of film, Precise thickness of film, multi component target, smooth surface, etc. He applied various characterization on that composite film like GIXRD, XRD, SEM, XPS and resulted that it is very low cost and highly effective method for Solar cell to enhance its efficiency. As discussed by the Lee *et al.*<sup>39</sup> SnO<sub>2</sub>-TiO<sub>2</sub> composite layer thin film is capable to produce efficiency near about 19.80%, same result is concluded by Song *et al.*<sup>40</sup> they claimed the highest PCE of 21.10%. The authors have been reported the approximate PCE upto 23% for perovskite solar cell with the spin coating method and sole gel methods for deposition of SnO<sub>2</sub> thin films and investigation of its properties by Comparing thermally annealed SnO<sub>2</sub> TF (T-SnO<sub>2</sub>) and P-SnO<sub>2</sub> TF<sup>41-42</sup>. Abdullah N *et al.*<sup>43</sup> performed an experiment with SnO<sub>2</sub> thin film solar cell in t four consecutive sunny days and resulted the highest solar radiation is 18.9%. Yang *et al.*<sup>44</sup> has been chosen EDTA to modify the SnO<sub>2</sub> to improve its performance. It is apparent that the unmodified EDTA and SnO<sub>2</sub> samples are transparent, while EDTA-treated SnO<sub>2</sub> turned into milky white. They developed an effective E-SnO<sub>2</sub> ETL by spin coating with the increased PCE of 21.60% with negligible hysteresis, This is the highest reported value for planar-type PSCs so far. They also fabricated solar cell at low temperature processing for E-SnO<sub>2</sub> ETLs, with high PCE of 18.28%. S Dolai *et al.*<sup>45</sup> fabricated Glass/F: SnO<sub>2</sub>/CdS/CuO/Ag structure heterojunction solar cell

with power conversion efficiency in between 2.0% and 2.1%. The authors used direct current (d.c.) magnetron sputtering and thermal evaporation technique for fabrication of solar cell. Liu R *et al.*<sup>46</sup> reported a high power efficiency of 16.85%. They used AZO substrate for fabrication of solar cell with addition of rGO in SnO<sub>2</sub> material. A brief description of SnO<sub>2</sub> material (photovoltaic application) is summarized in below Table 2.

## 5 Tin Oxide as Gas Sensors

Nowadays Gas sensors is the most fascinating research area because it is useful in monitoring environment issues according to the need for physical, chemical and biological systems in Earth's atmosphere. Researchers are working to enhance its durability, quick responsive, highly sensitive. Gas sensors playing an important role in the field of environment monitoring, medical applications, breath analysis for medical diagnoses, industrial applications, food processing, etc.<sup>47</sup>. Mainly the applications of gas sensors are to discriminate odor, to detect gas or to monitor changes in the particular gas in atmosphere. The selection of material is highly affected to performance of gas sensors. Metal oxide based gas sensors are the subject of research for last few decades because of its novel characteristic like band gap, electro conductivity, type of conductivity, oxygen diffusion etc. With strong oxidizing power, good chemical inertness, low cost, nontoxic, large surface area and unique optical property, nanostructured SnO<sub>2</sub> offer great potential for energy and environmental applications including gas sensing<sup>48</sup>. The analysis of many parameters of Tin oxides including different characterization is showing here in the below in Table 3.

Ryo Tanuma *et al.*<sup>49</sup> investigated that directly or indirectly CO<sub>2</sub> is affecting our daily life, so it is compulsory to have knowledge about concentration of CO<sub>2</sub> gas. To fulfill this purpose they developed CO<sub>2</sub> gas sensor having advantages of small size, low fabrication cost, better reliability, easy mass production etc. Ammonia (NH<sub>3</sub>) is a very harmful gas, which directly affected human health. Fluctuation of Ammonia gas can cause different diseases in human body like irritation in eyes, skin and human respiratory system, lung disease, blindness, kidney failure etc. Therefore, Beniwal A *et al.*<sup>47</sup> investigated a SnO<sub>2</sub> sensor for low concentration ammonia detection at room temperature. They prepared SnO<sub>2</sub>

Table 2 – A review of SnO<sub>2</sub> materials on preparation methods, characterization technique and photovoltaic application.

S.No.	Thin Film Material	Preparation Method	Characterization	Solar Cell	PCE	References
1.	LTP NCs SnO <sub>2</sub>	Spin Coating SnCl <sub>2</sub> .H <sub>2</sub> O	SEM, TEM, SAED, XPS, AFM, XRD	Perovskite	16.02%	Ke W. et al (2015) [28]
2.	Nd Doped SnO <sub>2</sub> Thin Film	Magnetron Sputtering	XRD, XPS, RBS, Hall Effect, TEM, PL	CIGS Solar cell	10.4% at (100- 400 <sup>0</sup> C)	Bouras K. et al (2016) [29]
3.	SnO <sub>2</sub> Thin Film	Sol- gel	XRD, SEM, TEM , PL	Perovskite	18.80%	Zhu Z. et al (2016) [30]
4.	SnO <sub>2</sub> and F doped SnO <sub>2</sub> Thin Film	Thermal evaporation & SP tech	XRD, SEM,I-V characteristics, TS	CDS & TCO Solar cell	High	Ikhmayies S. J.(2017) [31]
5.	SnO <sub>2</sub> -TiO <sub>2</sub> composite layer	Spin Coating	XRD, AFM , XPS, SEM	Perovskite	14.80%	Huang X.et al (2017) [32]
6.	SnO <sub>2</sub>	Sol- gel	SEM, J-V Curves, PL, XRD,IPCE	Perovskite	12.18%	Dong Q. et.al (2015) [33]
7.	SnO <sub>2</sub>	ALD	XRD, AFM , PL, SEM, TRPL	Perovskite	17.16%	Wang C.et al. (2016) [34]
8.	Mg doped SnO <sub>2</sub>	Spin Coating	XRD, SEM, XPS, UPS, Hall effect, IS	Perovskite	14.60%	Xiong L.et al (2016) [35]
9.	Ga doped SnO <sub>2</sub>	Sol- gel	XRD, XPS,SEM,	Perovskite	16.40%	Roose B. et al (2017) [36]
10.	Nb Doped SnO <sub>2</sub> Thin film	Spin Coating	XRD,AFM, XPS, SEM, PL	Perovskite	17.57%	Ren X. et al (2017) [37]
11.	ZnO-SnO <sub>2</sub> thin film	PLD	GIXRD, XRD, AFM, FESEM, XPS	Solar cell	High	Sinha S.K. (2016) [38]
12.	TiO <sub>2</sub> -SnO <sub>2</sub> Composite	Spin Coating	XRD, J-V curve, TEM, SEM,PL	Perovskite	19.80%	Lee Y. et al (2017) [39]
13.	TiO <sub>2</sub> -SnO <sub>2</sub> Composite thin film	Spin coating	XRD, HR-SEM, HR- TEM, UPS, SCLC, IPCE	Perovskite	21.10%	Song S. et al (2017) [40]
14.	Ta doped SnO <sub>2</sub> thin film	Spin coating	XRD, AFM, SEM, XPS, UVS, SE,	Perovskite	-	Ganchev M et al (2019) [41]
15.	SnO <sub>2</sub> thin film	Sol-gel	XPS, AFM, SPM, EDS	Perovskite	19.56%	Yu H. et al (2018) [42]
16.	SnO <sub>2</sub> thin film	Thermal Oxidation	FESEM, EDX, XRD,SEM,TEM, VLS	Solar cell	18.9%	N Abdullah et.al (2018) [43]
17.	EDTA complexed SnO <sub>2</sub> ETLs	Spin coating	XPS, FTIR, AFM, KPFM, SEM, PL, J-V curves	Perovskite	21.60%	Yang D. et al (2018) [44]
18.	EDTA complexed SnO <sub>2</sub> ETLs	Spin coating	XPS, FTIR, AFM, KPFM, SEM, PL, J-V curves	Perovskite	18.28% At low temp.	Yang D. et al (2018) [44]
19.	F:SnO <sub>2</sub> /CdS /CuO/Ag	Sputtering	XRD, FESEM, AFM, SAED,	F:SnO <sub>2</sub> /Ag CdS/CuO	2.1%	Dolai S. et.al (2019) [45]
20.	SnO <sub>2</sub> -rGO	Spin coating	SEM, AFM, PL	perovskite solar cells	16.87%	Liu R. et al (2018) [46]

thin film from sol-gel method and applied various characterizations on it like XRD, AFM, XPS, SEM. They concluded that it is very promising sensor to detect concentration of Ammonia at very low temperature and this sensor has various applications in future due to its excellent stability, proper recovery time and good response. Gupta P *et al.*<sup>50</sup> suggested that doping of Zn improve the gas sensing properties of SnO<sub>2</sub> like surface morphology, crystallinity, crystal size, etc. They reported that SnO<sub>2</sub> shows enhancement sensitivity for O<sub>2</sub> gas sensing among pure and Zn

doped SnO<sub>2</sub>. Khuspe G D *et al.*<sup>51</sup> reported in their study about more sensitivity and stability of SnO<sub>2</sub> towards NO<sub>2</sub> gas. They reported higher response of sensor is 19% and stability is 77.90%. Similarly Sharma A *et al.*<sup>2</sup> also investigated and find it highly sensitive. Ozone is an important gas which is using in many applications in today's physical world. Korotcenkov G *et al.*<sup>53</sup> have discussed about monitoring of Ozone (O<sub>3</sub>) gas in their paper. They compared SnO<sub>2</sub> and In<sub>2</sub>O<sub>3</sub> materials and also shown the advantage and disadvantage of SnO<sub>2</sub> thin film for

Table 3 – A review of SnO<sub>2</sub> materials on preparation methods, characterization technique and gas sensors application.

S.No.	Thin film material	Preparation Method	Characterization	Gas sensor	Response/ Sensitivity	References
1.	SnO <sub>2</sub> Thin Film	sol-gel	XRD, XPS, AFM and SEM	Ammonia (NH <sub>3</sub> ) gas	Response 28%	Beniwal A. et.al (2019) [47]
2.	SnO <sub>2</sub> Thin Film	RF sputtering method/ PLD	XRD, Vander Paw tech, optical transmittance	CO <sub>2</sub> gas sensor	Very high	Tanuma R. et.al (2018) [49]
3.	Zn-doped SnO <sub>2</sub>	sol-gel	XRD, PL, I-V, R-T, gas sensing measurement	O <sub>2</sub> gas	Sensitivity 37.6%	Gupta P. et.al (2017) [50]
4.	SnO <sub>2</sub> thin films	sol-gel	XRD, FESEM, TEM, IS, SAED	NO <sub>2</sub> gas	Response 19%	Khuspe G.D. et.al (2013) [51]
5.	SnO <sub>2</sub> thin film	RF sputtering method	XRD, AFM, XPS, SEM	NO <sub>2</sub> gas	Response 2.20x10 <sup>4</sup>	Sharma A. et.al (2013) [52]
6.	SnO <sub>2</sub>	spray pyrolysis	XRD, XPS, AFM and TEM	Ozone gas	Very high	Korotcenkov G. et.al (2012) [53]
7.	ZnO–SnO <sub>2</sub> composite	Spin coating	XRD, XPS, SEM, EDX	Hydrogen gas	Response 90% and high sensitivity	Mondal B. et.al (2013) [54]
8.	SnO <sub>2</sub> thin film	RF sputtering method	XRD, SEM	SO <sub>2</sub> gas	56	Tyagi P. et.al (2015) [55]
9.	Cu doped SnO <sub>2</sub> thin film	RF sputtering method	XRD, AFM, XPS, SEM	H <sub>2</sub> S gas	response 10.1 & recovery time 42.4S	Zhang S. et.al (2014) [56]
10.	Ni & Zn doped SnO <sub>2</sub>	screen-printing technique	XRD, XPS, SEM	CO gas	Response Ni -7.28 Zn- 5.90	Zhou Q. et.al (2017) [57]
11.	SnO <sub>2</sub> thin film	PLD	XRD, SEM,	CO & NO <sub>2</sub> gas	Response CO -5-50 ppm NO <sub>2</sub> - 0.5-1 ppm	Preiß M.E. et.al (2015) [58]
12.	SnO <sub>2</sub> nanocrystalline thin film	LB technique	FESEM, XPS, XRD	toxic gas	–	Betty C.A. et.al (2016) [59]
13.	Pd – SnO <sub>2</sub> thin film	RF Sputtering	XRD, UV-Visible	Methane gas	High response ~97.2%	Haridas D. et.al (2012) [60]
14.	SnO <sub>2</sub> thin film	Spray Pyrolysis	XRD, SEM, UV-Visible	NO <sub>2</sub> gas	–	Kamble D. L. et.al (2017) [61]
15.	Pt-doped SnO <sub>2</sub> thin film	RF sputtering	TEM, HRTEM,	HCHO, Toluene, and CO gas		Kang J. et.al (2017) [62]

Ozone gas sensor. Mondal B *et al.*<sup>54</sup> investigated ZnO-SnO<sub>2</sub> composite material based hydrogen sensor. It showed good selectivity and outstanding response of 90%. They also performed experiments on methane and Carbon-mono oxide gas but it showed good sensitivity for hydrogen gas. Tyagi P *et al.*<sup>55</sup> discussed in their paper about monitoring and deduction of most toxic and harmful gas SO<sub>2</sub>. They fabricated SO<sub>2</sub> gas sensors using SnO<sub>2</sub> thin film integrated with different metal oxide catalyst. Most highest response showed by the NiO<sub>2</sub> catalyst with SnO<sub>2</sub> thin film. For monitoring and deduction of toxic and inflammable gas Hydrogen Sulphide (H<sub>2</sub>S) S. Zhang *et al.*<sup>56</sup> resulted that Cu doped SnO<sub>2</sub> thin film is very suitable and promising alternative. It shows very high sensitivity, fine reproducibility, Quick response and short recovery time. Zhou Q *et al.*<sup>57</sup> reported rapid recovery and response time of Ni and Zn doped SnO<sub>2</sub>

gas sensors as compared to particular Zn doped or Ni doped SnO<sub>2</sub> nanomaterials. They applied various experiments on concentration of toxic CO gas and find better sensitivity and stability. Preiß E M *et al.*<sup>58</sup> performed their experiments on Tin Oxide films deposited at higher oxygen background pressure by PLD method to enhance sensor signal to CO. Author's resulted the response of sensors are 5-50 ppm for CO gas and 0.5-1 ppm for NO<sub>2</sub> gas at different operation temperatures and relative humidity. Betty C A *et al.*<sup>59</sup> reported in their paper that the gas sensitivity by nanocrystalline SnO<sub>2</sub> film sensor has been shown a visa-versa relationship with temperature for toxic gases such as H<sub>2</sub>S and SO<sub>2</sub> Haridas D *et al.*<sup>60</sup> investigated a high response of 97.2 % for detection of Methane gas. For sensor the thin film of SnO<sub>2</sub> material with Pd doping is synthesis by Rf- sputtering method. Kamble D L *et al.*<sup>61</sup>

experimented the nanocrystalline tin oxide ( $\text{SnO}_2$ ) thin films were synthesized with varying precursor concentrations of the solution by spray pyrolysis technique for  $\text{NO}_2$  gas detection. They applied XRD, SEM, UV-Visible and two probe resistivity characterization measurements on the prepared thin film. Kang J *et al.*<sup>62</sup> have performed experiment with Pt doped  $\text{SnO}_2$  thin film for CO, HCHO, and toluene gases. They concluded that on the 25 ppm toluene and HCHO gases are giving good selectivity response but CO gas is not showing any response

## 6 Results and Discussion

In the present work, the authors have studied current development on tin oxide. A study on different methods to prepare  $\text{SnO}_2$  thin films in pure form, composite form as well as doping with transition metals to display its structural and electrical properties have been put forward. Different Preparation methods of synthesis  $\text{SnO}_2$  films to highlight their utilities and drawbacks, various innovations and their unique effects, and potential applications especially towards photovoltaics and gas sensors have been discussed here. With so many useful applications of  $\text{SnO}_2$  thin films we are focusing only highly demanding application of photovoltaic and sensing application. Photovoltaic application is the most interesting application due to its specific advantages as a renewable energy source. It is very ecofriendly application which has no pollution and no green house gas emission.  $\text{SnO}_2$  has excellent properties of charge collection in Solar cells and having an effective and progressive scope in future green energy technology. Looking forward towards the futuristic aspects of  $\text{SnO}_2$  thin films the corresponding collected data as shown in Table 2 and presented by various authors have been also discussed and interpreted. A PCE of 16.02% has been achieved for low temperature nanocrystalline<sup>28</sup>  $\text{SnO}_2$ . Highest PCE of 19.56% were achieved for pure  $\text{SnO}_2$  thin films synthesized by different methods like sol-gel, ALD, spin coating, PLD and sputtering<sup>42</sup>. With the doping of Transition metals like Nb doped  $\text{SnO}_2$  thin film, Mg doped  $\text{SnO}_2$  thin film and Ga doped  $\text{SnO}_2$  thin film, the PCE's are 17.57%, 14.60%, 16.40%, respectively<sup>35-37</sup>. The investigation shows in case of Composite thin film of  $\text{SnO}_2$ - $\text{TiO}_2$  the achieved PCE<sup>40</sup> is 21.10%, which is the highest efficiency in all experiments.  $\text{SnO}_2$  as gas sensor application it is observable from the collected data as shown in Table 3 that pure  $\text{SnO}_2$  gas sensor fabricated by

Sputtering method is showing very high sensitivity for  $\text{CO}_2$  gas<sup>49</sup>. Similarly pure  $\text{SnO}_2$  thin films prepared by Sol-gel method are giving 28% response for Ammonia ( $\text{NH}_3$ ) gas and 19% response for  $\text{NO}_2$  gas<sup>47, 51, 52</sup>. With doping of Zn in  $\text{SnO}_2$  thin film an increased high response and sensitivity of 37.6% for the monitoring of  $\text{O}_2$  gas has been notified by the authors<sup>50</sup>.  $\text{SnO}_2$  thin film is good for Ozone gas sensing with high response<sup>53</sup>. Cu doped  $\text{SnO}_2$  is giving very quick recovery time for  $\text{H}_2\text{S}$  gas<sup>56</sup>. For  $\text{H}_2$  gas Authors obtained a very high response approximately 90% and high selectivity with the use of composite thin film of ZnO and  $\text{SnO}_2$  material<sup>54</sup>. For the monitoring of CO gas researchers performed their experiments with the doping of Ni and Zn and found the response of 7.28 and 5.90, respectively.  $\text{SnO}_2$  thin film fabricated by PLD method shows a response of 5-50 ppm for CO gas and 0.5 -1 ppm for  $\text{NO}_2$  gas, respectively<sup>58</sup>. An enhanced response (99.2%) for the detection of Methane gas can be obtained by  $\text{SnO}_2$  thin film in the presence of 10nm Pd clusters at the temperature of 160 °C<sup>60</sup>. Authors investigated the sensing characteristics to 25 ppm CO, 25 ppm toluene, and 1 ppm HCHO gases at 300-440 °C. They concluded the Pt-doped  $\text{SnO}_2$  gas sensors with the thickness of 120 nm showed the selectivity to 1ppm HCHO gas at 31.5 mW power consumption and to 25 ppm toluene gas<sup>62</sup> at 45 mW.

## 7 Conclusions

There are still substantial scopes in synthesis of  $\text{SnO}_2$  thin films by pulsed laser deposition method. It is worth mentioning that, among the other synthesis technologies, PLD method is the most suitable method because of the obvious reasons of accuracy, simplicity, flexibility, homogeneity and Uniformity. However, some of its benefits can be mentioned that by the fabrication of  $\text{SnO}_2$  thin film through PLD some important characterization like XPS and VBS study can be performed on the  $\text{SnO}_2$  materials. We hope that the study of this characterization technique may explore the new path of photovoltaic and gas sensor applications which can be helpful to achieve the desired efficiencies of solar cell for future aspects as well as excellent performance (gas response, selectivity, stability, sensitivity) in gas sensors.

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